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MANIPAL INSTITUTE OF TECHNOLOGY  
Manipal University



**SECOND SEMESTER M.Tech. (E & C) DEGREE END SEMESTER EXAMINATION  
MAY/JUNE 2016**

**SUBJECT: LARGE AREA MICROELECTRONICS (ECE - 562)**

**TIME: 3 HOURS**

**MAX. MARKS: 50**

**Instructions to candidates**

- Answer **ANY FIVE** full questions.
- Missing data may be suitably assumed.

- 1A. Can the principle of conservation of momentum holds good in amorphous solids? Explain the consequences for amorphous solids
- 1B. Describe how atomic structure determines electronic properties of amorphous solids.
- 1C. Describe the defects in the crystalline solids in terms of symmetry groups. How the concept of defects in amorphous solids is developed?

(3+3+4)

- 2A. Explain formation of band-gap in the amorphous solids. Explain how the bonding rule works in a-Si and a-Se.
- 2B. Describe chemical reactions involved in PECVD technique to grow a-Si:H.

(6+4)

- 3A. Explain PVD and CVD like regimes in plasma growth technique of a-Si material.
- 3B. Explain the leakage currents sources in PIN photodiodes.

(4+6)

- 4A. Describe how TFT influences the a-Si based photodetector.
- 4B. Derive an expression and plot the expression for current- voltage characteristics of a-Si TFT both for output and transfer functions.

(3+7)

- 5A. Describe how different capacitances in PIN photo diode pixel will influence its performance.
- 5B. What is quantum efficiency? Describe quantum efficiency of P-I-N diode with ITO contacts.
- 5C. Describe the following: i) Photovoltaic converter. ii) Pulse mode operation of TFT.

(3+3+4)

- 6A. Describe different techniques for charge separation in solar cells.
- 6B. Describe the following: i) Ideal photo converter. ii) Threshold voltage of a-Si:H TFT .

(5+5)